

(b) Amendment to the Claims

Please cancel claims 26 and 27 and add new claims 28 and 29 as follows.

The status of all the claims is listed below.

1. - 27. (Cancelled)

28. (Currently Amended) A plasma treatment apparatus for individually treating a plurality of reactors having different impedances comprising:
a plurality of different movable reactors each having an evacuable interior where at least one treatment cylindrical substrate is set, each movable reactor having an impedance different from ~~another of the plurality of different~~ that of the other movable reactors due to a different shape of the cylindrical substrate set in each movable reactor and each movable reactor configured to perform a different plasma treatment from another of the plurality of different movable reactors;

high-frequency power supply means for supplying high-frequency power into a selected movable reactor from the plurality of different movable reactors to cause glow discharge to take place in the selected movable reactor, the high-frequency power supply means having a connecting portion for connecting with the selected movable reactor;

~~one a plurality of~~ impedance matching ~~circuits each of which~~ circuit is provided to each of the plurality of different movable reactors, ~~each of the plurality of~~ the impedance matching ~~circuits~~ circuit configured to cause different impedances of the

corresponding plurality of different movable reactors to match an impedance of the high-frequency power supply means; and

moving means for moving the selected movable reactor into a plasma-treatment position in which the selected movable reactor is connected to the high-frequency power supply means via the impedance matching circuit provided to the selected movable reactor,

wherein the high-frequency power supply means is configured to individually and detachably connect to a movable reactor which is selected from the plurality of different movable reactors via one impedance matching circuit of the plurality of impedance circuits provided to each of the plurality of different moveable reactors.

29. (Previously Presented) The plasma treatment apparatus of claim 28, wherein the substrate is for an electrophotographic photosensitive member.